

CLAIMS

1. A semi-transmitting mirror-possessing substrate having a substrate, a foundation film formed on said substrate, and a semi-transmitting reflective film formed on said foundation film, the semi-transmitting mirror-possessing substrate characterized in that said foundation film is made to have a thickness in a range of 0 to 8nm.
2. A semi-transmitting mirror-possessing substrate as claimed in claim 1, characterized in that said foundation film is made of silicon oxide.
3. A semi-transmitting mirror-possessing substrate as claimed in claim 2, characterized in that a chemical composition ratio x of oxygen (O) to silicon (Si) in the silicon oxide (SiO_x) is in a range of 1.5 to 2.0.
4. A semi-transmitting mirror-possessing substrate as claimed in any one of claims 1 through 3, characterized in that said semi-transmitting reflective film is made of at least one selected from the group consisting of Al and Al alloys.
5. A semi-transmitting type liquid crystal display apparatus, characterized by having a semi-transmitting mirror-possessing substrate as claimed in any one of claims 1 through 4.